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ARTICLE TYPE

NaYF₄:Yb,Er/MoS₂: from synthesis, surface ligands-stripping, to negative infrared photoresponse

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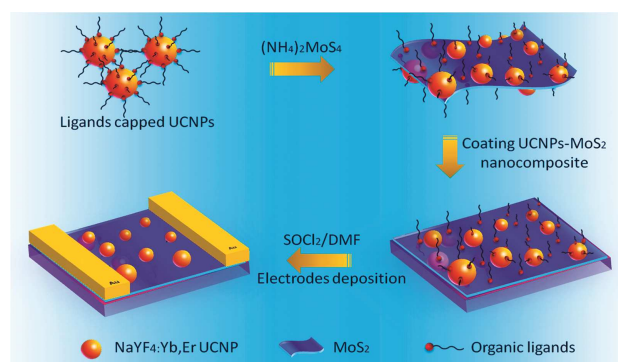
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The synthesis, surface ligands-stripping, and infrared optoelectronic device application of NaYF₄:Yb,Er-MoS₂ nanocomposites are reported. NaYF₄:Yb,Er-MoS₂ film shows unusual negative infrared photoresponse after SOCl₂/DMF treatment, which demonstrates more than 2 times photoresponsivity than pure NaYF₄:Yb,Er, showing great potential for the development of novel infrared optoelectronic devices.

Nanocomposites have attracted great attention in recent years because of their composition-dependent properties.¹ Multicomponent nanomaterials containing two or more nanoscale components often exhibit multiple functionalities, and the interaction between the components in such system may provide the functionality that extend beyond those of isolated materials and even exhibit novel properties, thus achieving potential applications in catalysis, optoelectronic and photovoltaic devices.² As a layered transition chalcogenide material, MoS₂ has shown great promise for the future electronic and catalytic applications in virtue of their unique structures, electrical and optical properties.³ In particular, the direct bandgap of mono- or few-layer MoS₂ suggests that it could be a promising material for optoelectronic applications.⁴ For example, MoS₂ nanosheet exhibits a high channel mobility (~200 cm²V⁻¹s⁻¹), photoresponsivity (880 AW⁻¹) and current On/Off ratio (10⁻⁸) in a phototransistor.^{4b,4c} However, the current MoS₂ optoelectronic devices show low if not negligible photoresponsivity to the light with wavelength >680 nm due to the weak absorption and intrinsic bandgap of MoS₂ nanosheet.^{4b-e} Therefore, it is essential to extend the device photoresponse to long wavelength region, to broaden its applicability.

On the other hand, upconversion nanoparticles, particularly lanthanide-doped rare-earth nanocrystals, are capable of absorbing infrared irradiation and emit high-energy photons due to the special configuration of 4f electrons in rare-earth elements.⁵ Among various upconversion materials, hexagonal NaYF₄:Yb,Er has been recognized as one of the most efficient UCNPs, showing potential applications in electronic devices, remote control devices and bioimaging.^{2,6} However, studies on the nanocomposite of NaYF₄:Yb,Er and MoS₂ nanosheet for optoelectronic device applications are still absent so far. In this paper, we present successful synthesis of NaYF₄:Yb,Er UCNPs-MoS₂ nanocomposites by a two-step thermolysis method in a mixture of oleic acid (OA) and oleylamine (OM) as described



Scheme 1 Schematic illustration of the synthesis of NaYF₄:Yb,Er UCNPs-MoS₂ nanocomposites and the fabrication of photoresponse devices.

in experimental section. Then, a new method of SOCl₂/DMF treatment was introduced to remove surface ligands of as-prepared materials for optoelectronic device application (Scheme 1). Photoresponse measurements revealed that these devices exhibited unusual negative photoresponsivity to infrared light, and NaYF₄:Yb,Er UCNPs-MoS₂ demonstrated much larger negative photoresponsivity than pure UCNPs.

Fig. 1 shows transmission electron microscopy (TEM) images of NaYF₄:Yb,Er UCNPs, MoS₂, and UCNPs-MoS₂ nanocomposites with a molar ratio of 1/0.2 of UCNPs/MoS₂. NaYF₄:Yb,Er UCNPs used for the synthesis of nanocomposites were monodispersed in spherical shape with a size of around 16 nm as shown in Fig. 1a. The prepared pure MoS₂ was in sheet nanostructure with few layers (Fig. 1b and S1†). Fig. 1c-e show typical TEM images of the obtained UCNPs-MoS₂ nanocomposites. It can be observed that UCNPs were anchored on MoS₂ nanosheets, and most of them were wrapped by loosely few layered MoS₂ as indicated by arrows in Fig. 1c-1d and S2 (ESI†). The average size of NaYF₄:Yb,Er particles were slightly increased to ~18 nm and some of them were in rod and irregular shape with multi-crystallite. This variation mainly resulted from Oswald ripening and coalescence growth at high temperature during the synthesis of composites.⁷ High resolution TEM (HRTEM) images (Fig. 1d and 1e) reveal lattice spacings of 0.3 and 0.65 nm, corresponding to the (110) facet of NaYF₄:Yb,Er and the (002) facet of MoS₂ sheet, respectively, indicating the anchor of UCNPs on MoS₂ nanosheets. As-prepared NaYF₄:Yb,Er-MoS₂ nanocomposites were also characterized by powder X-ray diffraction (XRD). The diffraction peaks and

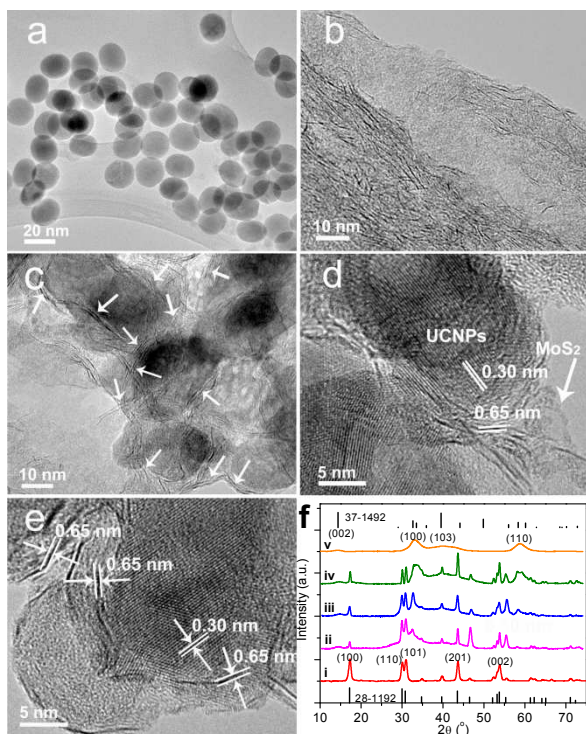


Fig. 1 TEM images of (a) NaYF₄:Yb,Er, (b) MoS₂, (c) NaYF₄:Yb,Er-MoS₂ (1/0.2), and (d, e) HRTEM images of nanocomposites. (f) XRD patterns of (f-i) NaYF₄:Yb,Er, (f-v) MoS₂, and NaYF₄:Yb,Er-MoS₂ nanocomposites prepared with different molar ratios of UCNP/MoS₂: (f-ii) 1/0.1, (f-iii) 1/0.2, (f-iv) 1/0.4.

intensities of pure NaYF₄:Yb,Er (Fig. 1f-i) match well with the standard pattern of hexagonal phase (JCPDS: 28-1192).^{5,6} For pure MoS₂, there are the broader peaks of (101), (103), (110) lattice planes (JCPDS: 37-1492),⁸ while the peak of (002) plane is weak, suggesting the predominated formation of few-layer MoS₂,⁸ which agrees well with TEM result. As for UCNP-MoS₂ composites, all samples showed the characteristic peaks of both NaYF₄:Yb,Er and MoS₂, and the peaks intensities of MoS₂ [e.g. (100), and (110)] gradually increased with increasing MoS₂ ratio (Fig. 1f-i-iv). In addition, the relatively higher emission of a physical mixture of UCNP and MoS₂ than their nanocomposite (Fig. S4†) further imply the close contact between NaYF₄:Yb,Er and MoS₂. Otherwise, UCNP-MoS₂ nanocomposites would give the same spectrum as that of their mixture (Fig. S4†). Furthermore, the excellent stability of the nanocomposites after surface ligands-removal (discussed below) further implies the strong interaction between UCNP and MoS₂ nanosheets. Therefore, in combination with HRTEM images, XRD and upconversion spectra, these results indicate the formation of NaYF₄:Yb,Er-MoS₂ nanocomposites.

Fig. 2a exhibits the upconversion emission spectra of the corresponding samples. It can be clearly observed that the characteristic emission bands of Er³⁺ ion were centred at 410, 520, 540 and 660 nm resulting from ⁴H_{9/2}→⁴I_{15/2}, ²H_{11/2}→⁴I_{15/2}, ⁴S_{3/2}→⁴I_{15/2} and ⁴F_{9/2}→⁴I_{15/2} transitions, respectively. The composite samples show a reduction in emission intensity in comparison with pure NaYF₄:Yb,Er, and the intensity of emission peaks decreased further with increasing the amount of MoS₂ in the samples. This is because the strong absorption of MoS₂ at a

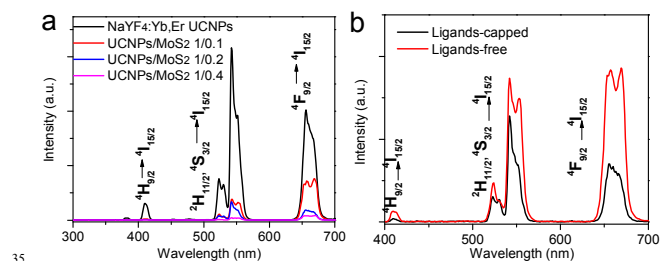
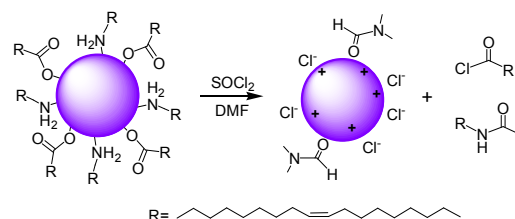


Fig. 2 Upconversion luminescence spectra of (a) NaYF₄:Yb,Er-MoS₂ composites with various molar ratios, and (b) NaYF₄:Yb,Er-MoS₂ (1/0.2) before and after ligands removal.



Scheme 2. Reactive ligands stripping of carboxylate- and amine-passivated nanomaterials with SOCl₂/DMF.

broad wavelength range from 300 to 700 nm covers emissions of NaYF₄:Yb,Er UCNP (Fig. S5†). The reduced lifetime indicates the existence of fluorescence resonance energy transfer and/or charge transfer procedure in nanocomposites (Fig. S6†). According to the data extracted, the energy-transfer efficiency of the composite is determined to be round 0.16, indicating radiative energy transfer due to photon re-absorption also take places.

In most cases, long hydrocarbon molecules containing a coordinating headgroup such as OA and OM were employed as surfactant ligands for controlled synthesis and stabilization of high-quality nanomaterials. The presence of these large organic molecules, however, creates an insulating shell around the surface, thus blocking charge transport and limiting their applications in electronic and optoelectronic devices.⁹ It is therefore necessary to remove these long-chain insulating ligands for practical device applications. In this work, a new approach for the removal of surface native ligands of as-prepared nanomaterials by using SOCl₂/DMF (namely Vilsmeier Reagent) is also presented, which can be completed in 2 min. SOCl₂ is a well-known chloridization agent, and can readily react with carboxylic acid, amine, alcohol *etc.* DMF is used as a catalyst to activate SOCl₂ and accelerate the reaction with surface ligands,¹⁰ thus achieving rapid removal of native ligands (Scheme 2). In the case that only SOCl₂ was added to the hexane dispersion of nanoparticles, no apparent precipitation was found even after ultrasonication for several minutes. On the contrary, rapid precipitation of nanoparticles were observed after addition of two drops of DMF with gentle shaking, indicating a dramatic change in material solubility as a result of induced surface modification.

Fourier transform infrared (FT-IR) spectra of the samples (Fig. 3) confirmed the removal of surface ligands. As expected, all samples before SOCl₂/DMF treatment exhibited strong characteristic absorption bands of alkyl chains of OA and OM (Fig. 3a-c): the asymmetric and symmetric stretching vibrations of methylene (CH₂ at 2924 and 2853 cm⁻¹, respectively) and carboxyl groups (COO⁻) at around 1564 cm⁻¹.¹¹ After treatment with SOCl₂/DMF, these signals were absent, confirming

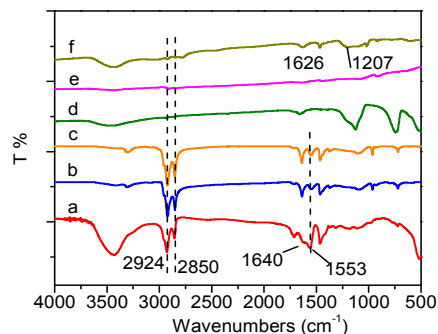


Fig. 3 FT-IR spectra of ligands-capped NaYF₄:Yb,Er, MoS₂, and NaYF₄:Yb,Er-MoS₂ composites before (a, b and c) and after (d, e and f) SOCl₂/DMF treatment, respectively.

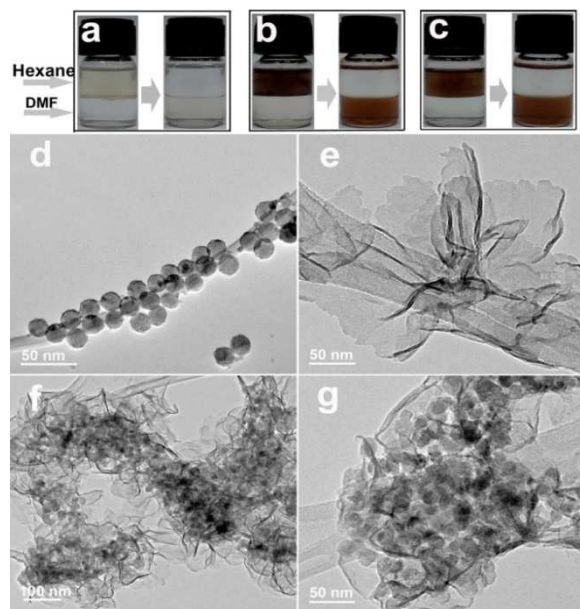


Fig. 4 Illustration of the phase-transfer of (a) NaYF₄:Yb,Er, (b) MoS₂, and (c) NaYF₄:Yb,Er-MoS₂ composites (1/0.2) from nonpolar solvent (hexane) to polar solvent (DMF) before and after SOCl₂/DMF treatment, and the corresponding TEM images of (d) NaYF₄:Yb,Er, (e) MoS₂ and (f, g) NaYF₄:Yb,Er-MoS₂ composites (1/0.2) dispersed in DMF after surface ligands removal.

complete removal of organic surfactants from nanomaterial surface. The resulting precipitate can be well redispersed in polar solvent such as DMF and DMSO (Fig. 4a-4c). Fig. 4d-4f exhibits the corresponding TEM images. For UCNP, the size and shape were preserved after treatment, and no obvious aggregation was observed upon surface modification (Fig. S7[†]). The shape of MoS₂ was slightly changed after treatment, and no initially loose layers were shown (Fig. 4e and S8[†]). Notably, the removal of organic ligands led to the variation of upconversion emission. For example, as compared to the untreated NaYF₄:Yb,Er-MoS₂ composite (1/0.2), all emission intensities of ⁴H_{9/2}→⁴I_{15/2}, ²H_{11/2}, ⁴S_{3/2}→⁴I_{15/2} and ⁴F_{9/2}→⁴I_{15/2} transitions in modified composites were much higher (Fig. 2b). This is because the removal of organic ligands with long-alkyl chain reduces the nonradiative relaxation of excited Er³⁺ ion from ²H_{11/2}/⁴S_{3/2} to ⁴F_{9/2} and ⁴I_{11/2} to ⁴I_{13/2} levels (Fig. S9),¹¹ thus enhancing emission intensities. The successful stripping and redispersion of UCNP, MoS₂ nanosheet and their composites passivated by either oleate or amine ligands imply the potential applications of this method for a variety of

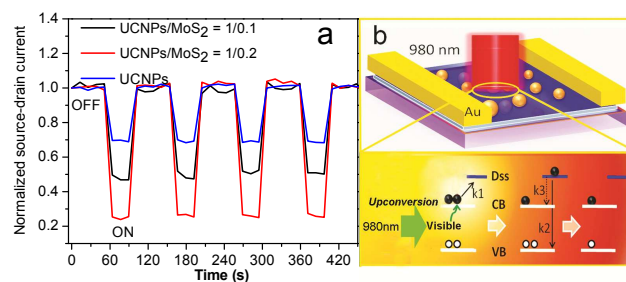


Fig. 5 (a) Real-time measurements of the normalized drain current of infrared photoresponse devices while the 980 nm infrared light is switched on and off with V_{DS} 10 mV at zero gate bias. UCNP and UCNP/MoS₂ (1/0.1, 1/0.2) represent the devices prepared with NaYF₄:Yb,Er UCNP and NaYF₄:Yb,Er-MoS₂ composite (1/0.1, 1/0.2) films treated with hexane solution of SOCl₂/DMF. (b) Schematic illustration of the device and the proposed mechanism of negative infrared photoresponse.

nanocrystals with different sizes, shapes, and surface ligands. Instead of tetrafluoroborates and metal chalcogenide complexes reported before,^{9,12} readily available SOCl₂/DMF is employed in this work, which was demonstrated to be a facile, rapid and efficient approach for the removal of native ligands while leaving the surface of nanomaterial bare and hydrophilic.

To demonstrate infrared photodetector application, photoresponse devices with the corresponding materials were fabricated. The photoresponses of these devices upon 980 nm infrared light irradiation were investigated. For the device fabrication, the films of surfactant ligands-capped nanomaterials were deposited on substrate, followed by immersion in a dilute solution of SOCl₂/DMF in hexane to remove the insulating organic ligands. Lastly, gold electrodes were deposited on top. Due to efficient removal of insulating ligands, favorable effect on the optoelectronic properties of the treated films is anticipated. Fig. 5a shows the time-dependent normalized drain current of the devices with a source-drain voltage (V_{DS}) of 10 mV at zero gate bias. Importantly, different from usually observed positive photocurrent response in semiconductor nanomaterials, unexpected *negative* photoresponse were exhibited in their films upon 980 nm infrared light irradiation (Fig. 5a, S10 and S11, ESI[†]). Once the incident light was removed, the current jumped back to the baseline level. Specifically, the photoresponse device with pure UCNP exhibited 30% decrease in I_d . For UCNP-MoS₂ nanocomposites, the device with a ratio of 1/0.1 of UCNP/MoS₂ exhibited a 50% decrease in source-drain current, and the one with a molar ratio of 1/0.2 showed up to 75% decrease (Fig. 5a), while no source-drain current was measured for 1/0.4 nanocomposite and pure MoS₂, due to the large cracks induced by the reduction of inter-nanosheet spacing after SOCl₂/DMF treatment (Fig. S12[†]).^{12a} It was indicated that the presence of MoS₂ in nanocomposites led to a stronger negative photoresponse, however, an excess amount of MoS₂ resulted in the formation of large cracks in the films after SOCl₂/DMF treatment, as a result, no source-drain current was measured.

Recently, Talapin *et al.* proposed a model to explain the negative photoconductivity in InAs nanocrystal film,^{9c} in which donorlike state form a localized level (D_{ss}) presumably located above the mobility edge. Photo-induced trapping of mobile electrons on this localized level (D_{ss}) resulted in negative photoconductivity. Such donorlike surface state has been

observed in semiconductor nanocrystals.¹³ This model is also a reasonable explanation for the experimentally observed negative photoresponses in this work (See ESI† for more details). We presume that the donorlike surface state is also formed in UCNP

5 and MoS₂ after surface treatment and locate above the mobility edge (Figure 5b). Upon 980 nm irradiation, a mobile electron is excited and gets trapped at D_{ss} level (k1), resulting in decreased conductivity. The electron trapped in D_{ss} state can either nonradiatively recombine with a hole in valence band (k2, VB) or

10 relax into the conduction band (k3, CB). When infrared light is off, electrons are no longer trapped and the conductivity is restored. Increasing the ratio of MoS₂ in hybrid composites may increase D_{ss} surface state due to the large specific area of nanosheet structure, thus causing stronger negative

15 photoresponse. The detailed mechanism is still under investigation.

In summary, the synthesis, surface ligands-stripping, and negative infrared photoresponse of new NaYF₄:Yb,Er UCNP-MoS₂ nanocomposites were demonstrated. The synthesis of

20 composites was achieved by thermolysis method in organic surfactant ligands. Then, we presented a new method using SOCl₂/DMF treatment to remove surface ligands of these nanomaterials for device applications, which was demonstrated to be a facile, rapid yet efficient approach for complete removal of

25 native ligands, showing potential applications for a variety of nanocrystals. Most importantly, after SOCl₂/DMF treatment, UCNP-MoS₂ nanocomposites films exhibited unexpected negative photoresponses to 980 nm illumination, and the photoresponsivity of UCNP-MoS₂ (1/0.2) was more than two

30 times of that of pure UCNP, indicating the potential application of these materials in infrared photoresponse devices. Also, this negative photoresponse phenomenon provides the opportunity for the development of novel optoelectronic devices.

Notes and references

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† Electronic Supplementary Information (ESI) available: Experimental section, HRTEM of MoS₂, TEM, SEM and absorbance spectra of ligands-capped UCNP-MoS₂ nanocomposites, upconversion spectra and TEM images of ligands-free UCNP-MoS₂, upconversion mechanism and infrared photoresponse measurements of nanocomposites. See DOI: 10.1039/b000000x/

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